

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-310485

(43)Date of publication of application : 04.11.1994

(51)Int.Cl.

H01L 21/304
H01L 21/68

(21)Application number : 05-097334

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(22)Date of filing : 23.04.1993

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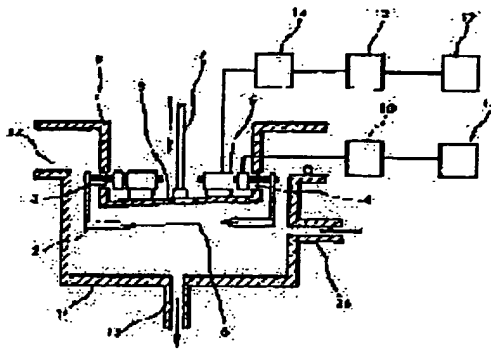
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(54) DUSTFREE CLAMPING METHOD FOR WAFER

(57)Abstract:

PURPOSE: To enable cleaning in a dustfree, low-stress, ultra clean environment by rectilinearly moving a plurality of clamping pawls to diagonally clamp a wafer, and separating a mechanical section from the clamping pawls on drive axis by means of a diaphragm.

CONSTITUTION: A cleaning equipment consists of a cleaning bath 1 and its lid 9 including the chamber 8 of a mechanism for driving pawls to clamp a wafer. The pawl driving mechanism chamber 8 consists of driving motors 5 and pressure sensors 4. The mechanism horizontally drives clamping pawls 2, separated therefrom by a diaphragm 3, on the cleaning bath 1 side to clamp a wafer. A plurality of the clamping pawls 2 are different from each other in length in the direction of opposite side. When receiving a wafer 6, therefore, the pawls 2 clamps it with a certain inclination. This obtains wafers free from spontaneous oxide films which are necessary in the development of devices with 0.3 μ m or below.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the
examiner's decision of rejection or application
converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

Searching PAJ

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[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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